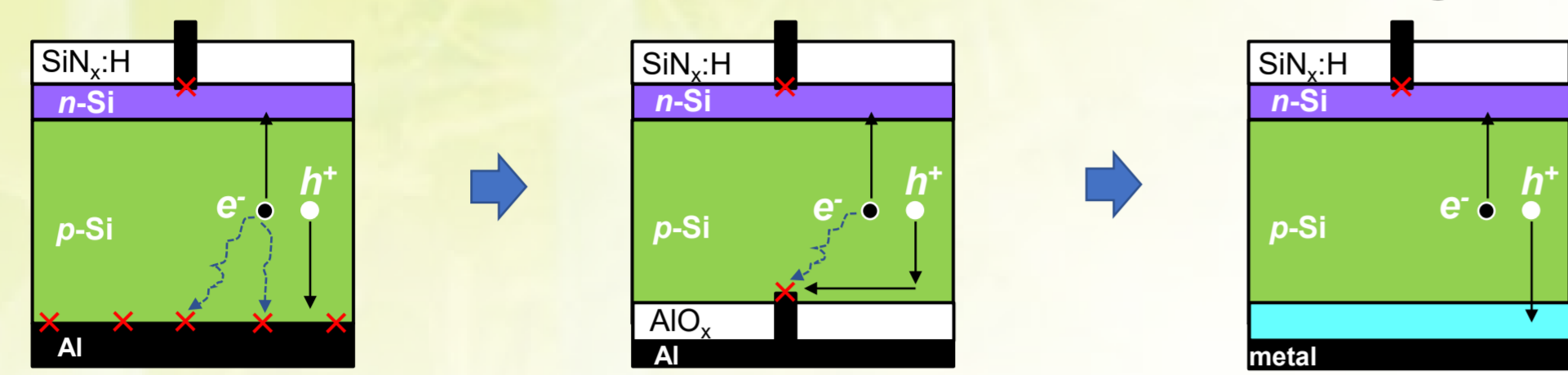


# Application of $\text{TiO}_x$ /metal bilayer as hole-selective passivating contact in crystalline silicon solar cells

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## Introduction

Al-BSF (Back Surface Field)      PERC      Passivating contact



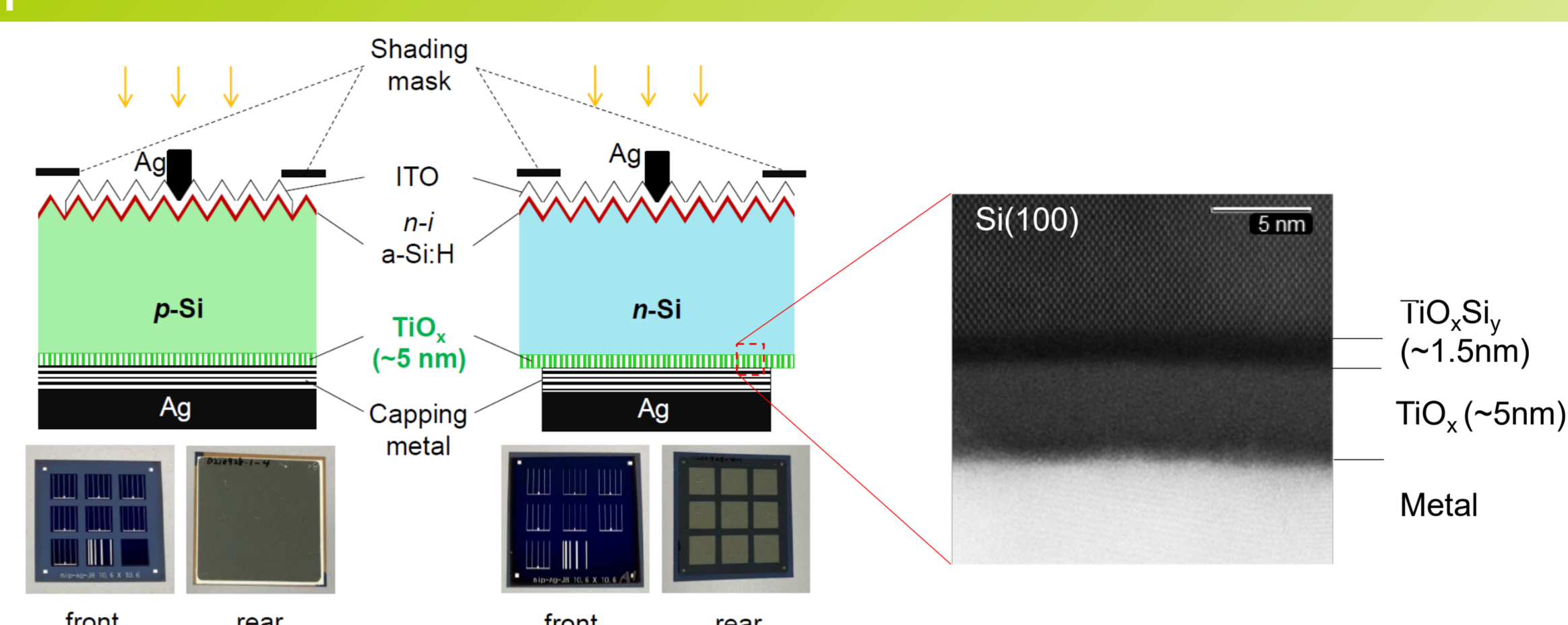
- Simplest process
- $\eta < 20\%$
- Rear passivation with partial Si/metal contact
- $\eta \sim 24\%$
- No direct Si/metal contact
- $\eta > 25\%$

Requirements of passivating contact [1]

1. Surface passivation
  2. Carrier selectivity
  3. Low contact resistivity
  4. Low optical loss
- Materials fulfilling these requirements are generally rare.
  - Currently, Si-based contact materials are available (SHJ, TOPCon).
  - Any non-Si material as good as Si-based contacts?

We have developed ALD- $\text{TiO}_x$  nanolayer that uniquely functions as an efficient hole-selective passivating contact [2]

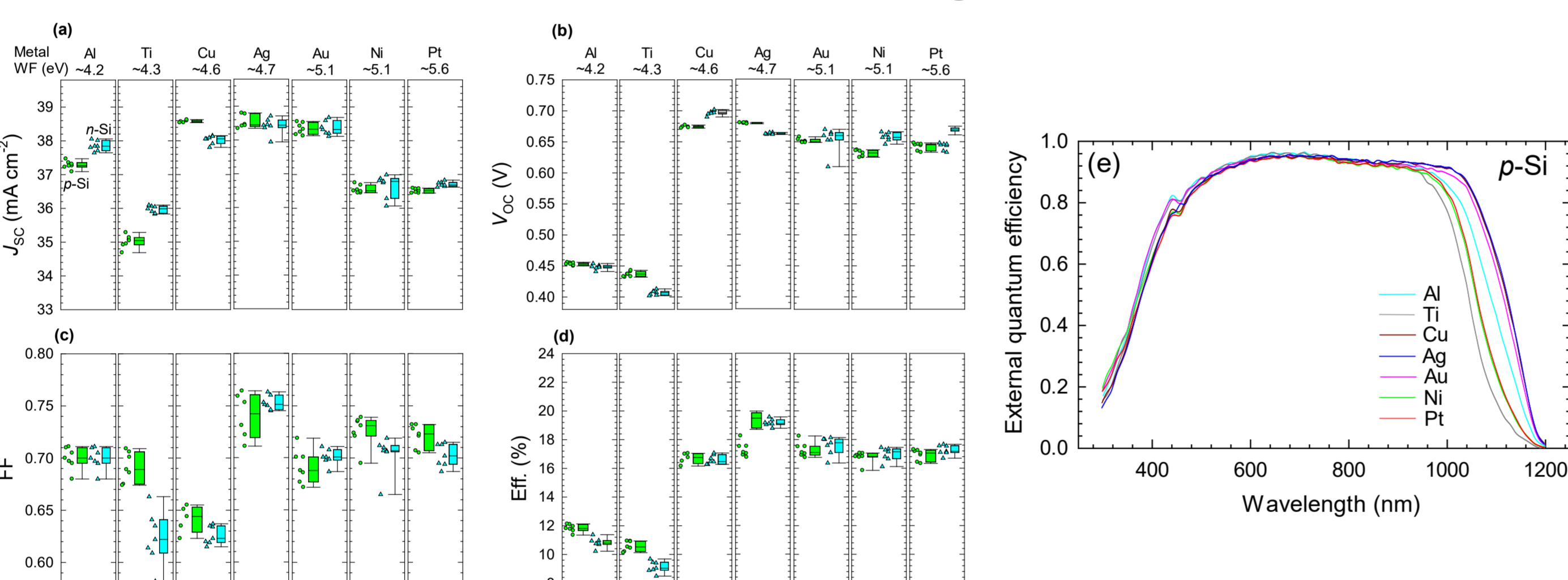
## Experiment



- Front texture and rear planar cells were fabricated (FJ for p-Si and RJ for n-Si) [3].
- ALD- $\text{TiO}_x$  hole contact layer ( $\sim 5$  nm) was deposited at the rear surface of p- and n-Si.
- $\text{TiO}_x$  was capped with 7 different metals (Al, Ti, Cu, Ag, Au, Ni, Pt) having a range of work functions (WF:  $\sim 4.2$ - $5.6$  eV), by DC sputtering or e-beam evaporation.
- No metal penetration through  $\text{TiO}_x$  layer is observed.

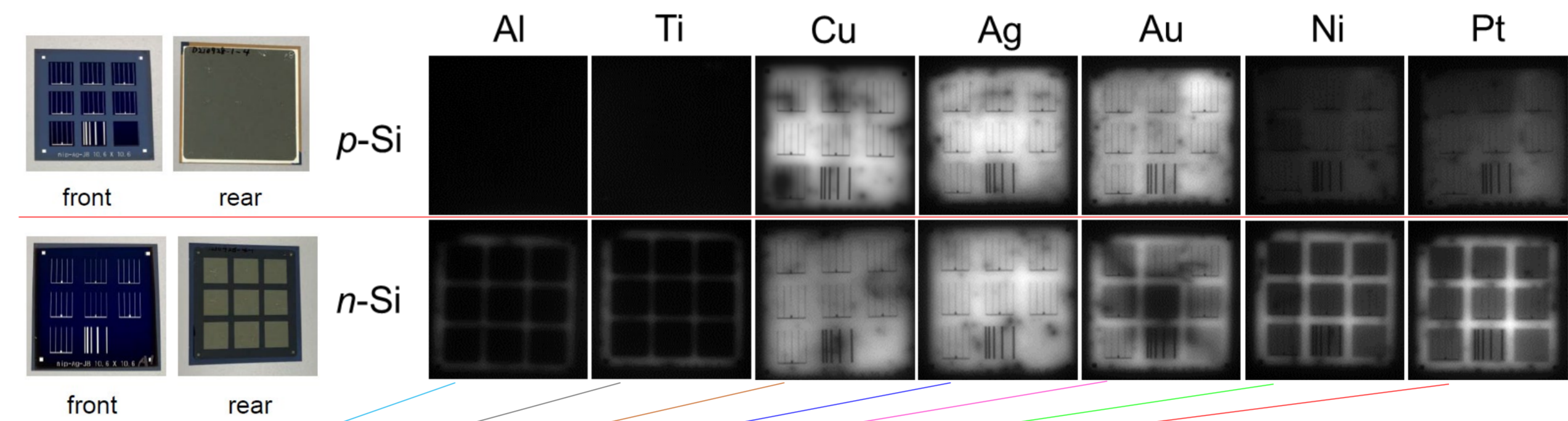
## Results and discussion I

### Impact of capping metal



- High  $J_{sc}$  is obtained when using metals exhibiting high infrared reflectivity (e.g. Al, Cu, Ag, Au).
- Abrupt change occurs in  $V_{oc}$  at WF  $\sim 4.3$ - $4.6$  eV.
- FF is less dependent on WF but some metal results in high and low FF.
- Efficiency is mostly determined by  $V_{oc}$ . Ag provides the best performing device.

### PL measurements on device



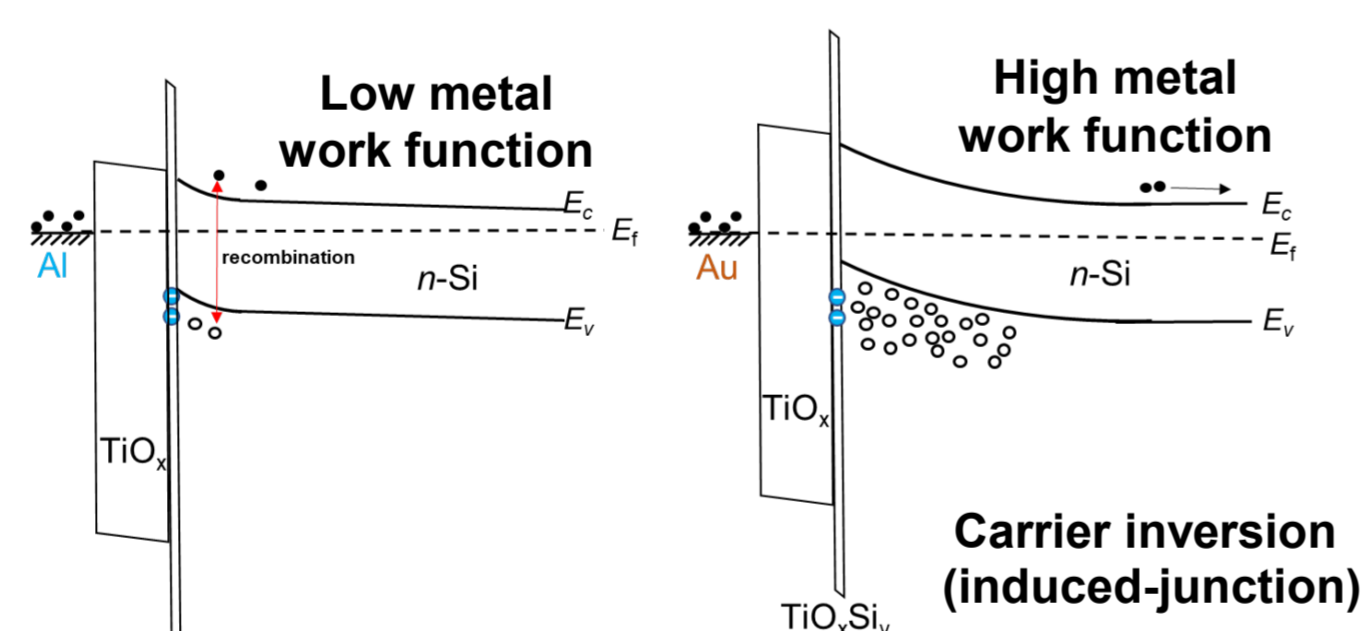
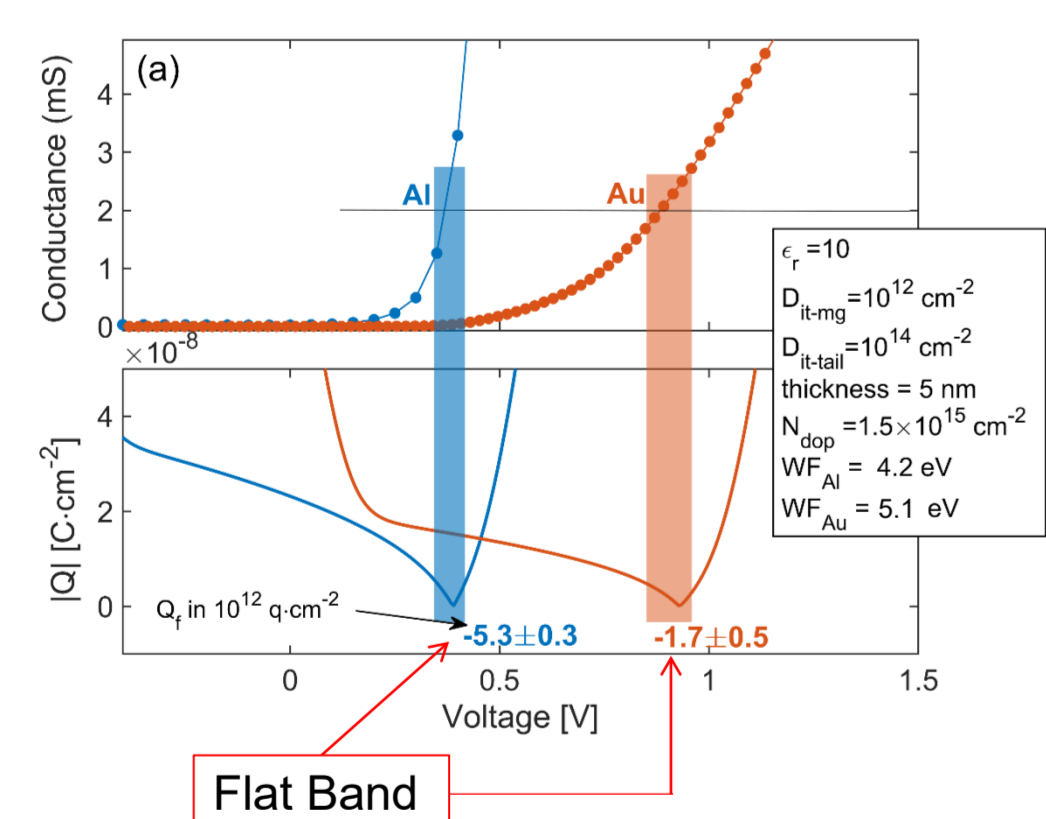
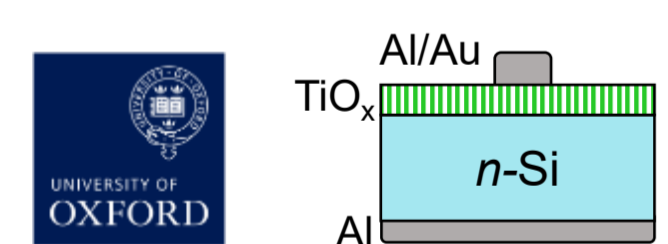
- High lifetime ( $> 3$  ms) was confirmed prior to metallization.
- PL measurements ( $\lambda = 850$  nm) was done on finished solar cells.
- PL signal intensity reflects passivation degree at the rear surface.
- Low-WF metals (Al, Ti): Passivation degradation occurs only for metallized area.
- High-WF metals: Relatively, high passivation performance obtained. PL reflected by the rear metal contributes to enhancing PL signal (Cu, Ag, Au).

PL signal intensity correlates well with  $V_{oc}$

## Results and discussion II

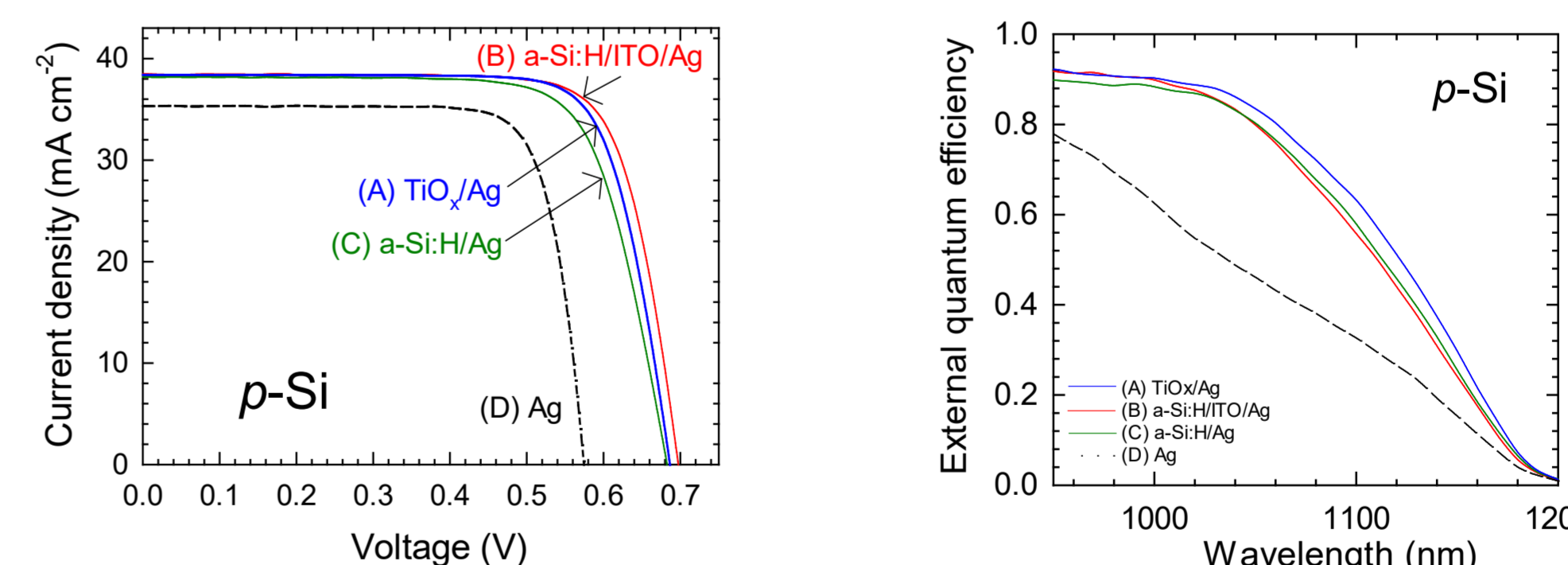
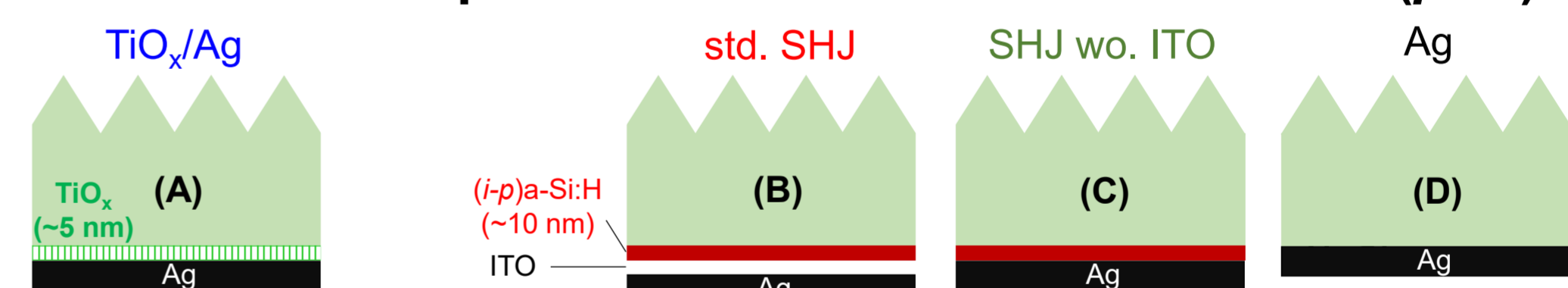
### Conductance-Voltage (G-V) measurements (conducted at Univ. Oxford)

Al and Au contacts on  $\text{TiO}_x$



- G-V: flat band occurs at higher voltages for high-WF metal ( $V_{FB}(\text{Al})$ :  $\sim 0.4$  V,  $V_{FB}(\text{Au})$ :  $\sim 0.9$  V).
- Analysis [4] indicates the presence of negative fixed charge ( $> 10^{12}$  cm<sup>-2</sup>) in the  $\text{TiO}_x$ , independent of the capping metal.
- Field-effect passivation is a major mechanism.
- High-WF metal is important to retain carrier inversion for n-Si (carrier accumulation for p-Si).

### Comparison with various rear contacts (p-Si)



- Comparable IV performance (20.3%, p-Si) with the conventional SHJ (a-Si:H i-p/ITO/Ag) rear contact.
- Similar result obtained for n-Si (rear junction) cell.
- Highest IR response.
- Efficiency is limited by the low  $J_{sc}$  due to parasitic absorption of front layers (ITO, a-Si:H i-n).

## Conclusion & Next plan

- ALD- $\text{TiO}_x$  is applied to the rear of Si solar cells as a full-area hole-selective passivating contact.
- Passivation is greatly influenced by the WF of capping metal. WF  $> 4.6$  eV is essential to retain field-effect passivation and hole selectivity.
- $\text{TiO}_x/\text{Ag}$  contact performs as high as SHJ with an improved infrared reflectivity. Proof-of-concept devices show 20% efficiency for both p-Si and n-Si solar cells.
- $\text{TiO}_x/\text{metal}$  as an alternative contact in PERC is proposed, which is expected to provide less process complexity and improved performance (e.g., from 2D to 1D carrier transport and higher infrared reflectivity).

## References

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